

IN THE CLAIMS:

1. (Currently Amended) A gate electrode structure comprising:  
a silicon-containing film ~~formed on a gate insulating film and~~ containing silicon as a principal constituent;  
a barrier metal layer of titanium nitride rich in titanium as compared with a stoichiometric ratio formed on said silicon-containing film; and  
a metal film with a high melting point formed on said barrier metal layer<sub>1</sub>[[.]]  
wherein said gate electrode structure is formed on a gate insulating film.
2. (Currently Amended) A gate electrode structure comprising:  
a silicon-containing film formed on a gate insulating film and containing silicon as a principal constituent;  
a first barrier metal layer of titanium nitride rich in titanium as compared with stoichiometric ratio formed on said silicon-containing film;  
a second barrier metal film of titanium nitride including nitrogen in a ratio not less than a stoichiometric ratio formed on said first barrier metal layer; and  
a metal film with a high melting point formed on said second barrier metal layer<sub>1</sub>[[.]]  
wherein said gate electrode structure is formed on a gate insulating film.
3. (Currently Amended) A method for fabricating a gate electrode structure comprising the steps of:  
forming, ~~on a gate insulating film,~~ a silicon-containing film containing silicon as a principal constituent;  
forming, on said silicon-containing film, a barrier metal layer of titanium nitride rich in titanium as compared with a stoichiometric ratio;  
forming a metal film with a high melting point on said barrier metal layer, whereby forming a multi-layer film including said silicon-containing film, said barrier metal layer and said metal film with a high melting point; and  
patterning said multi-layer film into ~~an~~ said gate electrode structure<sub>1</sub>[[.]]  
wherein said gate electrode structure is formed on a gate insulating film.

4. (Previously Presented) The method for fabricating a gate electrode structure of Claim 3,

wherein step of forming said barrier metal layer includes a sub-step of using a target of titanium nitride rich in titanium as compared with a stoichiometric ratio and causing discharge in an inert gas including substantially no nitrogen, whereby depositing, on said silicon-containing film, the titanium nitride rich in titanium as compared with the stoichiometric ratio sputtered out from said target.

5. (Previously Presented) The method for fabricating a gate electrode structure of Claim 3,

wherein step of forming said barrier metal layer includes a sub-step of using a target of titanium including substantially no nitrogen and causing discharge in a mixed gas of a nitrogen gas and an inert gas with a partial pressure ratio of the nitrogen gas lower than a nitriding point of said target, whereby depositing, on said silicon-containing film, titanium nitride rich in titanium as compared with a stoichiometric ratio formed through a reaction between titanium sputtered out from said target and nitrogen ions included in said mixed gas.

6. (Previously Presented) A method for fabricating a gate electrode structure comprising the steps of:

forming a silicon-containing film containing silicon as a principal constituent;

forming, on said silicon-containing film, a barrier metal layer of titanium nitride rich in titanium as compared with a stoichiometric ratio;

forming a metal film with a high melting point on said barrier metal layer, whereby forming a multi-layer film including said silicon-containing film, said barrier metal layer and said metal film with a high melting point; and

patterning said multi-layer film into an electrode structure,

wherein no titanium silicide layer is formed on said silicon-containing film through annealing carried out on said electrode structure at a temperature of 600 or more.

7. (Currently Amended) A method for fabricating a gate electrode structure comprising the steps of:

forming, ~~on a gate insulating film~~, a silicon-containing film containing silicon as a principal constituent;

forming, on said silicon-containing film, a first barrier metal layer of titanium nitride rich in titanium as compared with a stoichiometric ratio;

forming, on said first barrier metal layer, a second barrier metal layer of titanium nitride including nitrogen in a ratio not less than a stoichiometric ratio;

forming a metal film with a high melting point on said second barrier metal layer, whereby forming a multi-layer film including said silicon-containing film, said first barrier metal layer, said second barrier metal layer and said metal film with a high melting point; and

patterning said multi-layer film into ~~an~~ said gate electrode structure,[[.]]

wherein said gate electrode structure is formed on a gate insulating film.

8. (Previously Presented) The method for fabricating a gate electrode structure of Claim 7,

wherein the step of forming said first barrier metal layer included a sub-step of using a target of titanium nitride rich in titanium as compared with a stoichiometric ratio and causing discharge in an inert gas including substantially no nitrogen, whereby depositing, on said silicon-containing film, the titanium nitride rich in titanium as compared with the stoichiometric ratio sputtered out from said target, and

the step of forming said second barrier metal layer includes a sub-step of using said target and causing discharge in a mixed gas of a nitrogen gas and an inert gas with a partial pressure ratio of the nitrogen gas not less than a nitriding point of said target, whereby forming, on said target, a titanium nitride film rich in titanium as compared with the stoichiometric ratio and depositing, on said first barrier metal layer, the titanium nitride rich in titanium as compared with the stoichiometric ratio sputtered out from said titanium nitride film formed on said target.

9. (Previously Presented) The method for fabricating a gate electrode structure of Claim 7,

wherein the step of forming said first barrier metal layer included a sub-step of using a target including substantially no nitrogen and causing discharge in a mixed gas of a

nitrogen gas and an inert gas with a partial pressure ratio of the nitrogen gas lower than a nitriding point of said target, whereby depositing, on said silicon-containing film, titanium nitride rich in titanium as compared with a stoichiometric ratio formed through a reaction between titanium sputtered out from said target and nitrogen ions included in said mixed gas, and

the step of forming said second barrier metal layer includes a sub-step of using said target and causing discharge in a mixed gas of a nitrogen gas and an inert gas with a partial pressure ratio of the nitrogen gas not less than the nitriding point of said target, whereby forming, on said target, a titanium nitride film rich in titanium as compared with a stoichiometric ratio and depositing, on said first barrier metal layer, the titanium nitride rich in titanium as compared with the stoichiometric ratio sputtered out from said titanium nitride film formed on said target.

10. (Previously Presented) A method for fabricating a gate electrode structure comprising the steps of:

forming a silicon-containing film containing silicon as a principal constituent;

forming, on said silicon-containing film, a first barrier metal layer of titanium nitride rich in titanium as compared with a stoichiometric ratio;

forming, on said first barrier metal layer, a second barrier metal layer of titanium nitride including nitrogen in a ratio not less than a stoichiometric ratio;

forming a metal film with a high melting point on said second barrier metal layer, whereby forming a multi-layer film including said silicon-containing film, said first barrier metal layer, said second barrier metal layer and said metal film with a high melting point; and

patterning said multi-layer film into an electrode structure,

wherein no titanium silicide layer is formed on said silicon-containing film through annealing carried out on said electrode structure at a temperature of 600 or more.